

## ABSTRACT

A lithographic apparatus includes an illumination system for providing a beam of radiation, a support structure for supporting a patterning device, the patterning device serving to impart the beam with a pattern in its cross-section. The apparatus further includes a substrate table for holding a substrate, a projection system for projecting the patterned beam onto a target portion of the substrate, and a collector which is arranged for transmitting radiation, received from a first radiation source, to the illumination system. The apparatus includes at least a heater for heating the collector when the collector receives substantially no radiation from the first radiation source. Further aspects of the invention relate to a device manufacturing method as well as a device manufactured thereby.